CLAIMS

What is claimed is:

1   1.   A method of producing a critical dimension value comprising:

2   determining a stepper focus;

3   combining said stepper focus with a critical dimension measurement; and

4   generating said critical dimension value from said combining.

    2.   The method of claim 1, wherein said step of determining a stepper focus

comprises:

        navigating to a stepper focus monitor target;

        performing a scanning electron microscope focusing; and

        performing a final alignment of said target.

1   3.   The method of claim 2, wherein said step of determining a stepper focus further

2   comprises:

3   acquiring a waveform data;

4   analyzing said waveform data; and

5   determining said stepper focus based on said analyzing.

1   4.   The method of claim 2, wherein said step of determining a stepper focus further

2   comprises:

3   acquiring an image data;

4   analyzing said image data; and

5   determining said stepper focus based on said analyzing.

1   5.   The method of claim 1, wherein said step of generating a critical dimension value

2   comprises:

3   navigating to a critical dimension structure;

4   performing a scanning electron microscope focusing; and

5   performing a final alignment of said structure.

1   6.   The method of claim 5, wherein said step of generating a critical dimension value

2   further comprises:

3   acquiring a waveform data;

4   analyzing said waveform data; and

5   determining said critical dimension value based on said analyzing.

1   7.   The method of claim 5, wherein said step of generating a critical dimension value

2   further comprises:

3   acquiring an image data;

4   analyzing said image data; and

5   determining said critical dimension value based on said analyzing.

1   8.   A method of producing a critical dimension value comprising:

2   generating a scanning electron microscope focus;

3   generating a waveform data based on output from said scanning electron

4   microscope focus;

5   analyzing said waveform data to determine a critical dimension measurement;

6   analyzing said waveform data to determine a stepper focus parameter;

7   combining said stepper focus parameter with said critical dimension

8   measurement; and

9   generating said critical dimension value from said combining.

1   9.   The method of claim 8, wherein said step of generating a waveform data further

2   comprises:

3   navigating to a critical dimension structure;

4   performing a scanning electron microscope focusing;

5   performing a final alignment of said structure; and

6   acquiring said waveform data based on said scanning electron microscope

7 focusing and said final alignment.

1   10.   A method of producing a critical dimension value comprising:

2   generating a scanning electron microscope focus;

3   generating an image data based on output from said scanning electron microscope

4 focus;

5   analyzing said image data to determine a critical dimension measurement;

6   analyzing said image data to determine a stepper focus parameter;

7   combining said stepper focus parameter with said critical dimension

8 measurement; and

9   generating said critical dimension value from said combining.

1   11.   The method of claim 10, wherein said step of generating an image data further

2 comprises:

3   navigating to a critical dimension structure;

4   performing a scanning electron microscope focusing;

5   performing a final alignment of said structure; and

6   acquiring said image data based on said scanning electron microscope focusing

7 and said final alignment.

1	12.	A method of producing a critical dimension value comprising:

2		determining a stepper focus;

3		measuring a critical dimension measurement;

4		combining said stepper focus with said critical dimension measurement; and

5		generating said critical dimension value based on said combining.

1	13.	The method of claim 12, wherein said step of determining a stepper focus

2	comprises:

3		navigating to a stepper focus monitor target;

4		performing a scanning electron microscope focusing; and

5		performing a final alignment of said target.

1	14.	The method of claim 13, wherein said step of determining a stepper focus further

2	comprises:

3		acquiring a waveform data;

4		analyzing said waveform data; and

5		determining said stepper focus based on said analyzing.

1   15.   The method of claim 13, wherein said step of determining a stepper focus further

2   comprises:

3   acquiring an image data;

4   analyzing said image data; and

5   determining said stepper focus based on said analyzing.

1   16.   The method of claim 12, wherein said step of generating a critical dimension

2   value comprises:

3   navigating to a critical dimension structure;

4   performing a scanning electron microscope focusing; and

5   performing a final alignment of said structure.

1   17.   The method of claim 16, wherein said step of generating a critical dimension

2   value further comprises:

3   acquiring a waveform data;

4   analyzing said waveform data; and

5   determining said critical dimension value based on said analyzing.

1   18.   The method of claim 16, wherein said step of generating a critical dimension

2   value comprises:

3   acquiring an image data;

4   analyzing said image data; and

5   determining said critical dimension value based on said analyzing.

1   19.   A method of producing a critical dimension value comprising:

2   determining a stepper focus;

3   measuring a critical dimension measurement;

4   combining said stepper focus with said critical dimension measurement; and

5   generating said critical dimension value based on said combining;

6   wherein said step of determining a stepper focus further comprises:

7   navigating to a stepper focus monitor target;

8   performing a scanning electron microscope focusing at said target;

9   performing a final alignment of said target based on said scanning electron

10   microscope focusing at said target;

11   acquiring a first data set from said scanning electron microscope focusing;

12   analyzing said first data set; and

13   determining said stepper focus based on said analyzing;

14   wherein said step of generating a critical dimension further comprises:

15   navigating to a critical dimension structure;

16   performing a scanning electron microscope focusing at said critical

17   dimension structure;

18   performing a final alignment of said critical dimension structure;

19   acquiring a second data set from said scanning electron microscope

20   focusing at said critical dimension structure;

21   analyzing said second data set; and

22   determining a critical dimension value based on said analyzing.

1 20. A program storage device readable by machine, tangibly embodying a program of

2 instructions executable by the machine to perform a method of producing a critical dimension

3 value, said method comprising:

4   determining a stepper focus;

5   combining said stepper focus with a critical dimension measurement; and

6   generating a critical dimension value from said combining.

1 21. The program storage device of claim 20, wherein said step of determining a

2 stepper focus comprises:

3   navigating to a stepper focus monitor target;

4   performing a scanning electron microscope focusing; and

5   performing a final alignment of said target.

1 22. The program storage device of claim 21, wherein said step of determining a

2 stepper focus further comprises:

3   acquiring a waveform data;

4   analyzing said waveform data; and

5   determining said stepper focus based on said analyzing.

1 23. The program storage device of claim 21, wherein said step of determining a

2 stepper focus further comprises:

3   acquiring an image data;

4   analyzing said image data; and

5   determining a stepper focus based on said analyzing.

1   24.   The program storage device of claim 20, wherein said step of generating a critical

2 dimension value comprises:

3   navigating to a critical dimension structure;

4   performing a scanning electron microscope focusing; and

             performing a final alignment of said structure.

25.   The program storage device of claim 24, wherein said step of generating a critical

2 dimension value further comprises:

             acquiring a waveform data;

3   analyzing said waveform data; and

5   determining said critical dimension value based on said analyzing.

1   26.   The program storage device of claim 24, wherein said step of generating a critical

2 dimension value further comprises:

3   acquiring an image data;

4   analyzing said image data; and

             determining said critical dimension value based on said analyzing.